

RESPONSE UNDER 37 C.F.R. § 1.116
EXPEDITED PROCEDURE
EXAMINING GROUP 2800

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants: *Gabric, et al.* Docket No.: INF 2006 VJ 33543 US
Serial No.: 10/586,788 Art Unit: 2893
Filed: September 2, 2008 Examiner: Nikolay K. Yushin
Conf. No.: 1598
For: Plasma Excited Chemical Vapor Deposition Method
Silicon/Oxygen/Nitrogen-Containing-Material and Layered Assembly

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

RESPONSE UNDER 37 CFR § 1.116

Dear Sir:

Applicants respectfully submit the following amendments and remarks in response to Examiner's Office Action dated November 4, 2009, which Action is made final. Applicants respectfully request that these amendments and remarks be entered pursuant to the provisions of 37 CFR § 1.116, and respectfully request reconsideration of claims 21-36, and 38.